

JPM



Docket No.: 055071-0328

PATENT

IN THE UNITED STATES PATENT AND TRADEMARK OFFICE

Re Application of : Customer Number: 20277
Robert John SOCHA, et al. : Confirmation Number: 2388
Application No.: 10/756,829 : Group Art Unit: 1756
Filed: January 14, 2004 : Examiner: Yet to be assigned
:

For: METHOD OF OPTICAL PROXIMITY CORRECTION DESIGN FOR CONTACT HOLE MASK

SUPPLEMENTAL INFORMATION DISCLOSURE STATEMENT

Mail Stop IDS
Commissioner for Patents
P.O. Box 1450
Alexandria, VA 22313-1450

Dear Sir:

In accordance with the provisions of 37 C.F.R. 1.56, 1.97 and 1.98, the attention of the Patent and Trademark Office is hereby directed to the documents listed on the attached form PTO-1449. It is respectfully requested that the documents be expressly considered during the prosecution of this application, and that the documents be made of record therein and appear among the "References Cited" on any patent to issue therefrom.

This Information Disclosure Statement is being filed within three months of the U.S. filing date OR before the mailing date of a first Office Action on the merits. No certification or fee is required.

10/756,829

Please charge any shortage in fees due in connection with the filing of this paper,
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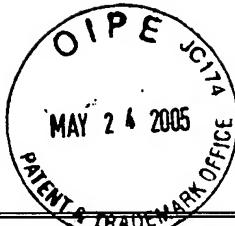
Respectfully submitted,

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SHEET 1 OF 1

**INFORMATION DISCLOSURE
CITATION IN AN
APPLICATION**

(PTO-1449)

ATTY. DOCKET NO.
055071-0328SERIAL NO.
10/756,829**APPLICANT****Robert John SOCHA, et al.**FILING DATE
January 14, 2004GROUP
1756**U.S. PATENT DOCUMENTS**

EXAMINER'S INITIALS	CITE NO.	Document Number Number-Kind Code(s) (if known)	Publication Date MM-DD-YYYY	Name of Patentee or Applicant of Cited Document	Pages, Columns, Lines, Where Relevant Passages or Relevant Figures Appear
	US	5,680,588	10-21-1997	Gortych et al.	
	US	6,563,566 B2	05-13-2003	Rosenbluth et al.	
	US	5,446,521	08-29-1995	Hainsey et al.	
	US	5,532,090	07-02-1996	Borodovsky	
	US	5,595,843	01-21-1997	Dao	
	US	5,620,816	04-15-1997	Dao	
	US				

FOREIGN PATENT DOCUMENTS

EXAMINER'S INITIALS	CITE NO.	Foreign Patent Document Country Code(s)-Number +-Kind Codes (if known)	Publication Date MM-DD-YYYY	Name of Patentee or Applicant of Cited Document	Pages, Columns, Lines Where Relevant Figures Appear	Translation Yes No

OTHER ART (Including Author, Title, Date, Pertinent Pages, Etc.)

EXAMINER'S INITIALS	CITE NO.	Include name of the author (in CAPITAL LETTERS), title of the article (when appropriate), title of the item (book, magazine, journal, serial, symposium, catalog, etc.), date, page(s), volume-issue number(s), publisher, city and/or country where published.	
		KENNY K.H. TOH, ET AL., "Design Methodology for Dark-Field Phase-Shifted Masks," SPIE Vol. 1463 Optical/Laser Microlithography IV (1991), p. 402-413.	
		RICHARD SCHENKER, ET AL., "Alternating Phase Shift Masks for Contact Patterning," Proceedings of SPIE Vol. 5040 Optical Microlithography XVI (2003), p. 294-302.	

EXAMINER

DATE CONSIDERED

*EXAMINER: Initial if reference considered, whether or not citation is in conformance with MPEP 609. Draw line through citation if not in conformance and not considered.
Include copy of this form with next communication to applicant.

1 Applicant's unique citation designation number (optional). 2 Applicant is to place a check mark here if English language Translation is attached.